

L Number	Hits	Search Text	DB	Time stamp
1	115733	(etch\$3 remov\$3) near5 oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/12 05:25
2	96857	trench adj2 isolation STI?	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/12 05:26
3	114281	silicon adj nitride	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/12 05:27
4	836	((etch\$3 remov\$3) near5 oxide) same (trench adj2 isolation STI?) same (silicon adj nitride)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/12 05:27
5	15388	oxide near5 trench\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/12 05:27
6	469	((etch\$3 remov\$3) near5 oxide) same (trench adj2 isolation STI?) same (silicon adj nitride)) same (oxide near5 trench\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/12 05:28
7	17555	remov\$3 near5 oxide?	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/12 05:28
8	24892	implant\$4 near5 impurit\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/12 05:30
9	13	(remov\$3 near5 oxide?) same (implant\$4 near5 impurit\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/12 05:30
10	2	((etch\$3 remov\$3) near5 oxide) same (trench adj2 isolation STI?) same (silicon adj nitride)) same (oxide near5 trench\$2)) and ((remov\$3 near5 oxide?) same (implant\$4 near5 impurit\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/12 05:30